

## Combined Measurement Results of dedicated RD50 Charge Multiplication Sensors

*Tuesday 4 June 2013 12:00 (20 minutes)*

In this talk the combined results of dedicated charge multiplication sensors, produced by MICRON (UK) within the CERN RD50 framework, and measured at Freiburg and Liverpool are presented. The sensors vary in device thickness, in strip pitch and width as well as in diffusion times and energies for the implantation process. Some of the sensors have additional intermediate strips (biased or floating) between the readout strips. They were irradiated with neutrons to fluences of  $1E15$  and  $5E15$   $1 \text{ MeV neq/cm}^2$ . The collected charge is measured with the ALiBaVa setup to investigate the effect of charge multiplication for the different sensor geometries/properties.

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